## Thermomechanical properties and glass dynamics of polymer tethered colloidal particles and films

Yu Cang<sup>1</sup>, Anna N. Reuss<sup>1</sup>, Jaejun Lee<sup>2</sup>, Jiajun Yan<sup>3</sup>, Jianan Zhang<sup>2,3</sup>, Elena Alonso-Redondo<sup>1</sup>, Rebecca Sainidou<sup>4</sup>, Pascal Rembert<sup>4</sup>, Krzysztof Matyjaszewski<sup>3</sup>, Michael R. Bockstaller<sup>2</sup>, George Fytas<sup>1</sup>

<sup>1</sup>Max Planck Institute for Polymer Research, Ackermannweg 10, 55128 Mainz, Germany

<sup>2</sup>Department of Materials Science and Engineering, Carnegie Mellon University, 5000 Forbes Avenue, Pittsburgh,

PA, 15213, USA

<sup>3</sup>Chemistry Department, Carnegie Mellon University, 4400 Fifth Avenue, Pittsburgh, PA 15213, USA

<sup>4</sup>Normandie Univ, UNIHAVRE, Laboratoire Ondes et Milieux Complexes, UMR CNRS 6294, University of Le Havre,

75 Rue Bellot, 76600 Le Havre, France

\*) corresponding authors: bockstaller@cmu.edu, fytas@mpip-mainz.mpg.de



Figure S1. SEM images (Scale bar: 200 nm) of particle brushes measured before and after annealing process.

The key parameter  $\phi_{PS}$  of samples is determined independently by five different methodologies shown as following.

1. By calculating the brush volume from the grafting density, the density of bulk PS (1050 kg/m<sup>3</sup>), the interparticle distance (d) and radius of silica (R), where d and R were obtained from the TEM images:

$$V_{PS} = \frac{4\pi R^2 \sigma Mn}{\rho_{PS} V_A}, \quad V_{SiO2} = \frac{4\pi R^3}{3}, \quad V_{Brush} = \frac{4\pi (\frac{d}{2})^3}{3}$$
$$\Phi_{PS-1} = \frac{V_{PS}}{V_{PS}+V_{SiO2}}, \quad \Phi_{PS-2} = \frac{V_{PS}}{V_{Brush}}$$

2. Calculation based on the assumption of a FCC assembly structure, where diameter of particle brush (d) and radius of silica (R) are determined from TEM images:

$$\Phi_{ps-3} = 1 - V_{silica} = 1 - \frac{4\sqrt{2\pi R^3}}{3d^3}$$

3. From the individual particle brushes, using the dimension of singe particle brush (d) as obtained from the SEM images and radius of silica (R) obtained from TEM images:

$$\Phi_{PS-4} = 1 - \frac{(2R)^3}{d^3}$$

4. From thermogravimetric analysis of brush particle solids that yields the volume fraction of inorganic component from the amount of solid that is retained after pyrolysis of the materials. The organic (PS) weight fraction can be calculated subsequently as follows:

$$\Phi_{PS-5} = 1 - \frac{\Phi_{SiO_2,wt} \cdot \rho_{PS}}{\left(1 - \Phi_{SiO_2,wt}\right) \cdot \rho_{SiO_2} + \Phi_{SiO_2,wt} \cdot \rho_{PS}}$$

Table S1. Volume fraction of polystyrene is determined by different methods

	$arPsi_{ extsf{PS-1}}$	$\varPhi_{ extsf{PS-2}}$	$arPsi_{ extsf{PS-3}}$	arPs-4	$arPsi_{ extsf{PS-5}}$	$arPhi_{average ext{-PS}}$
DP1300	0.85	0.67	0.91	0.87	0.82	0.86±0.04
DP2480	0.89	0.63	0.94	0.93	0.90	0.93±0.03
DP530	0.54	0.45	0.72	0.54	0.56	0.56±0.02
DP1170	0.44	0.52	0.50	0.49	0.47	0.50±0.02
DP100	0.41	0.36	0.62	0.72	0.41	0.48±0.04



**Figure S2**. Evolution of eigenmode spectra of DP1170 (a) and DP2480 (c) with increasing temperature. The peak frequency (low panel) and linewidth (upper panel) of the strongest modes for DP1170 (b) and DP2480 (d) are plotted as a function of temperature. The vertical shaded area in (b,d) indicates the glass transition region in DP1170.



**Figure S3.** (a) Polarized (VV) and depolarized (VH) BLS spectra of PS2k (Molecular weight 2000 g/mol) at 295K. (b) The variation of Poisson's ratio with temperature. (The Poisson's ratio:  $v = \frac{C_L^2 - 2C_T^2}{2(C_L^2 - C_T^2)}$ )

![](_page_4_Figure_2.jpeg)

**Figure S4.** (a) Evolution of eigenmode spectra of DP100 with increasing temperature. (b) Temperature dependence of the peak frequency (low panel) and linewidth (upper panel) of the strongest mode in the DP100 spectra. The vertical shaded area indicates the glass transition region.

T <sub>g</sub> /K	DP1300	DP2480	DP530	DP1170
4 <sup>st</sup> D	343	358	354	349
1" Run	352	379	381	382
	373			
2 <sup>nd</sup> Run	353	382	353	382
			381	
3 <sup>rd</sup> Run	356	382	362	382
			382	

Table S2. Summary of  $T_{\rm g}$  of particle brush systems as determined by DSC.

![](_page_5_Figure_2.jpeg)

**Figure S5.** DSC traces of particle brush systems recorded during heating (cooling) of materials at a rate of 10 K /min (20 K / min, see text for more details) representing the 1<sup>st</sup> run (red), 2<sup>nd</sup> run (green), and 3<sup>rd</sup> run (blue). Glass transition temperatures are indicated by arrows and summarized in Table

S1.

	Particles			Film		
Sample	Tg	$lpha_g$	α_m	Tg	$lpha_{g}$	α_m
	(К)	(-10 <sup>-4</sup> K <sup>-1</sup> )	(-10 <sup>-3</sup> K <sup>-1</sup> )	(K)	(-10 <sup>-4</sup> K <sup>-1</sup> )	(-10 <sup>-3</sup> K <sup>-1</sup> )
DP530	355±4	6.3±0.2	1.51±0.07	363±2	5.7±0.3	1.02±0.04
DP1170	353±3	6.6±0.6	1.62±0.03	360±3	5.9±0.5	1.01±0.01
DP1300	-	6.5±0.5	-	367±3	5.3±0.1	0.98±0.01
DP2480	-	9.2±0.6	-	356±3	4.0±0.1	1.00±0.02

**Table S3.** Thermomechanical properties as determined from BLS experiments.

![](_page_6_Figure_2.jpeg)

Figure S6. TEM images of particle brush films with scale bar  $1\mu m$  (left panel) and 200 nm (right panel).

![](_page_7_Figure_0.jpeg)

**Figure S7**. The TEM images show the microstructure of DP2480 (a) before and (b) after an annealing process. The annealing process was taken at 130 °C for 2h. The corresponding distributions of areas of Voronoi cell elements (marked in the TEM images with yellow polygon) (c) before and (d) after the annealing process were shown in histograms. The normal distribution (red line in figure c and d) is fitted with Gaussian distribution to estimate the deviation. The similar microstructure in the TEM images and average area suggest no structural changes after the thermal annealing process.

Sample	A×10 <sup>3</sup> (m/s) ( <i>T</i> <7 <sub>g</sub> )	B×10 <sup>5</sup> (mK/s) ( <i>T</i> < <i>T</i> <sub>g</sub> )	A×10 <sup>3</sup> (mK/s) ( <i>T</i> >7 <sub>g</sub> )	B×10⁵ (mK/s) ( <i>T</i> >7 <sub>g</sub> )
DP1300	-1.7	2.0	0.2	9.1
DP2480	-1.9	1.5	0.06	8.0
DP530	-1.9	2.6	0.3	10.5
DP1170	-2.1	2.8	0.2	10.9
PS-30K	-1.9	1.4	0.6	10.5

**Table S4.** The parameters A and B of particle brush films.

A and B are the intercept and slope in the equation. ( $c_L = \frac{B}{T} - A$ )